Impact of On-Chip Multi-Layered Inductor on Signal and Power Integrity of Underlying Power-Ground Net

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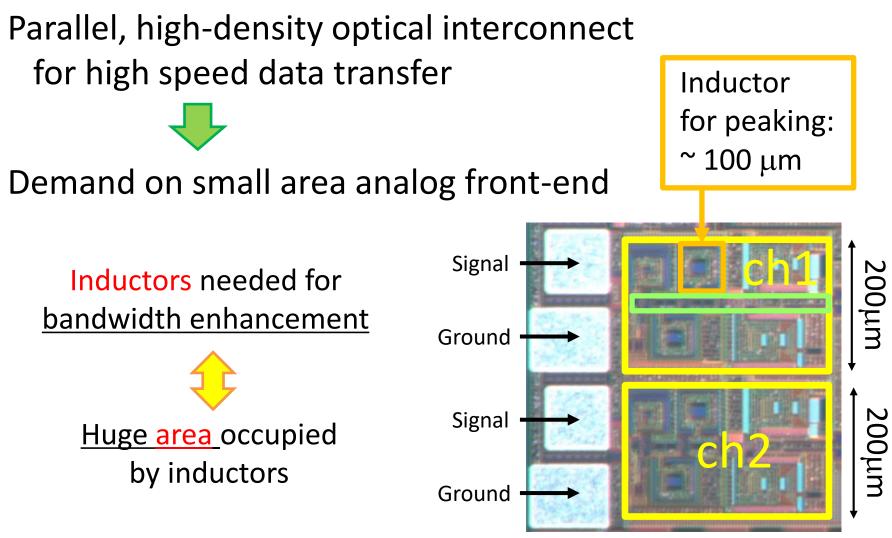
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Agenda

- Background and motivation
- Simulation setup
- Simulation results
- Conclusion and future work

Background

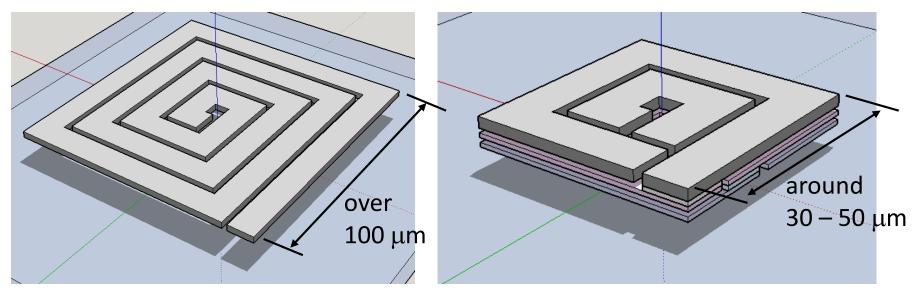


TIA + Post amp. 3

Small Area Inductor

Spiral Inductor

Solenoid Inductor



✓ Top (Thick) metal only✓ High Q-factor

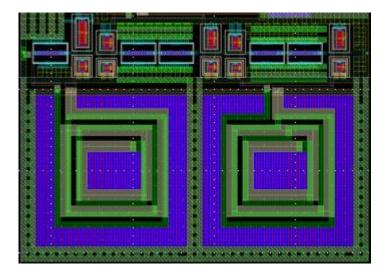
✓ Huge area

✓ Use lower layers
✓ Low Q-factor
✓ Small area

Solenoid inductor is effective for inductive peaking

More Area-Saving

Is it OK to stack inductor on circuits?



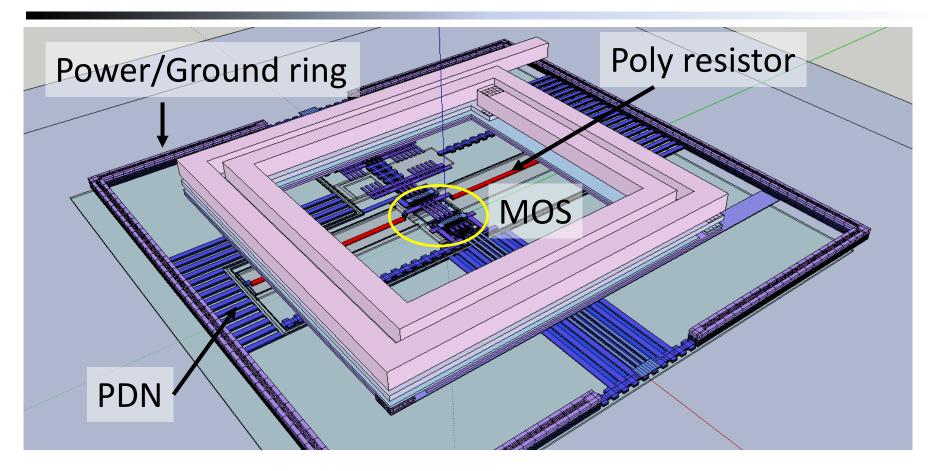
Solenoid is smaller, but still needs >50µm□

Nothing under inductor

- ✓ Modeling accuracy
- ✓ Prevent coupling

If stacking is OK, we can save area more Aim of this paper: Investigating coupling between inductor and PDN

Stacking Inductor on Circuit

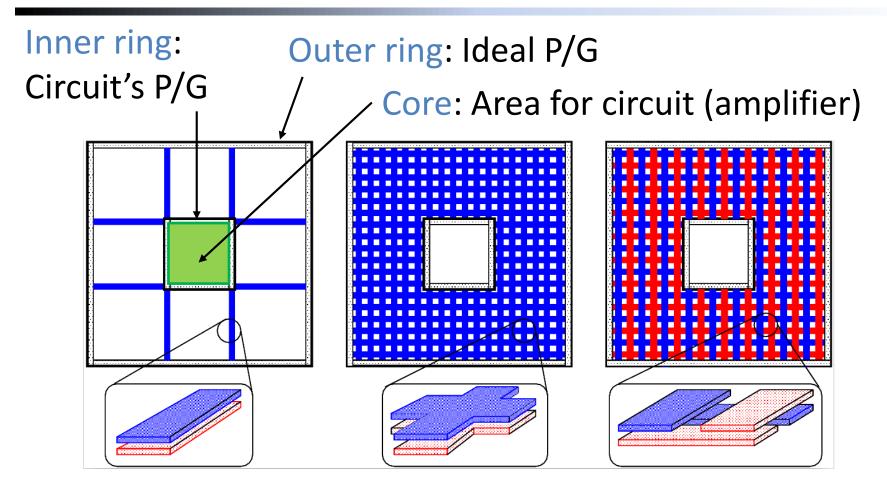


Largest facing area to inductor is PDN (power delivery network) How should we design PDN under inductor?

Agenda

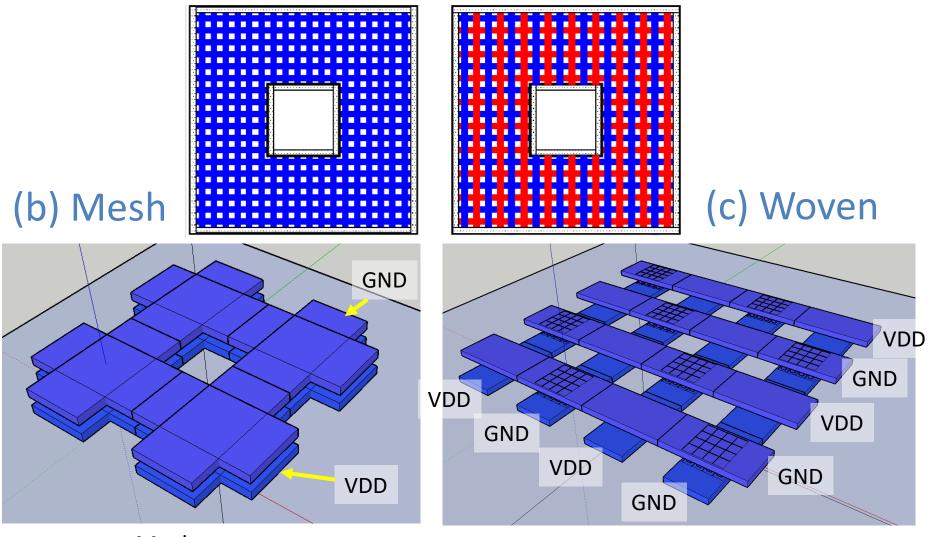
- Background and motivation
- Simulation setup
 - Power/Ground network structure
 - Structure of inductor
- Simulation results
- Conclusion and future work

Power/Ground Structure



(a) Sparse (b) Mesh (c) Woven

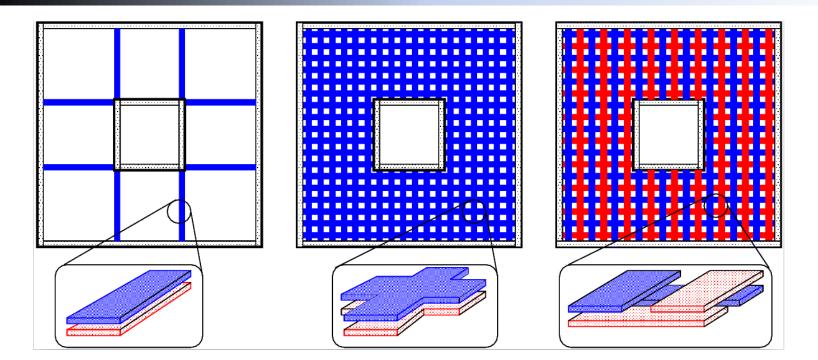
3D Image of Mesh and Woven



Mesh structure

Woven structure

Comparison



(a) Sparse Minimize C coupling Small decoupling

(b) Mesh

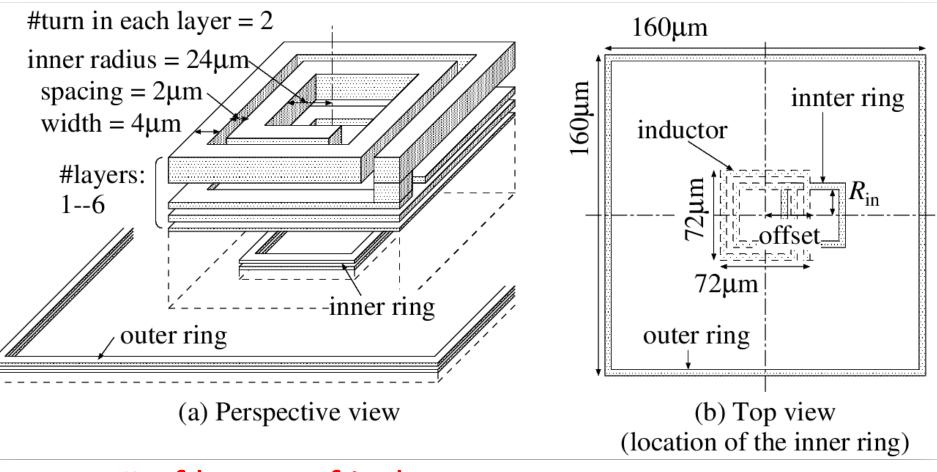
M2 (GND) couples stronger Large decoupling

(c) Woven

Couplings are balanced Large decoupling

* decoupling: decoupling capacitance between Vdd and GND 10

Parameters

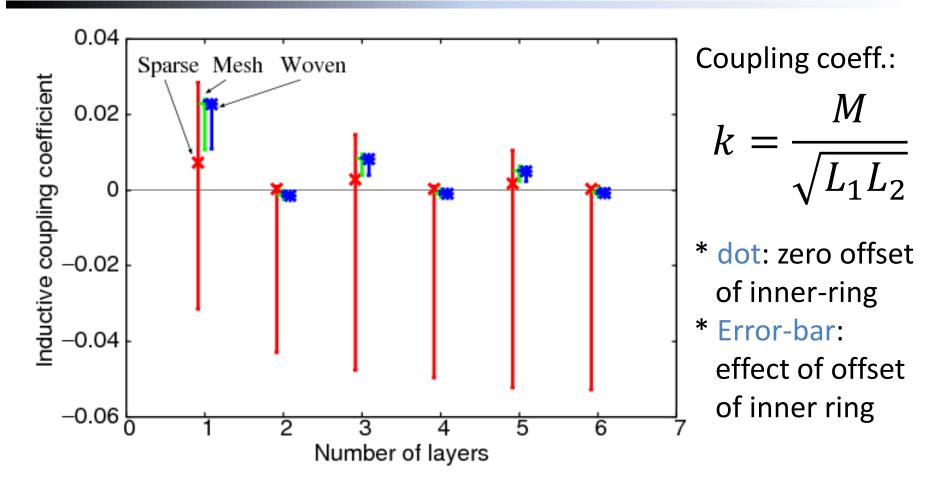


of layers of inductor Size and position of inner ring (core area)

Agenda

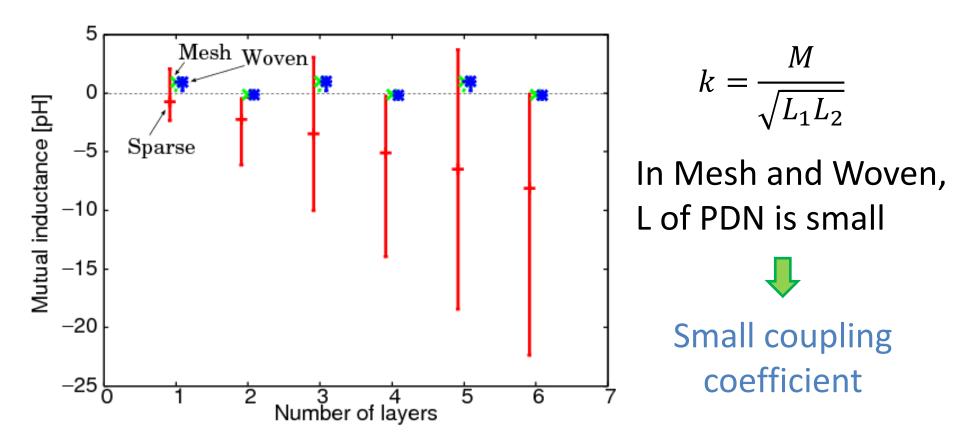
- Background and motivation
- Simulation setup
- Simulation results
 - Evaluation in inductance/capacitance value
 - Evaluation in transient analysis
- Conclusion and future work

Inductive Coupling (Coupling Coeff.)



Increasing #layers = inductor get closer to PDN, but In Mesh and Woven, coupling coeff. decreases

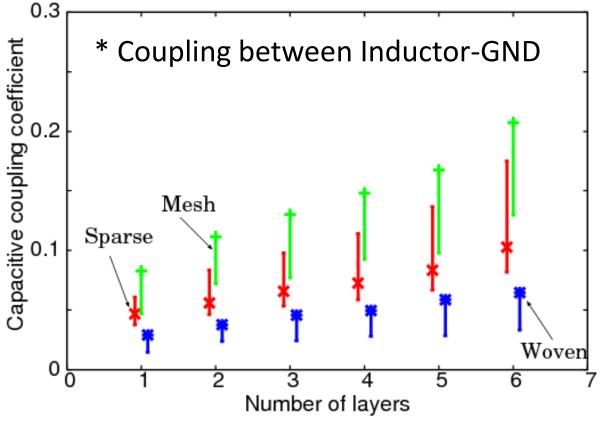
Inductive Coupling (Mutual Inductance)



Dense PDN can make inductive coupling almost zero even #layer increases

Capacitive Coupling (Coupling Coeff.)

Much larger than inductive coupling coefficient (< 0.05)

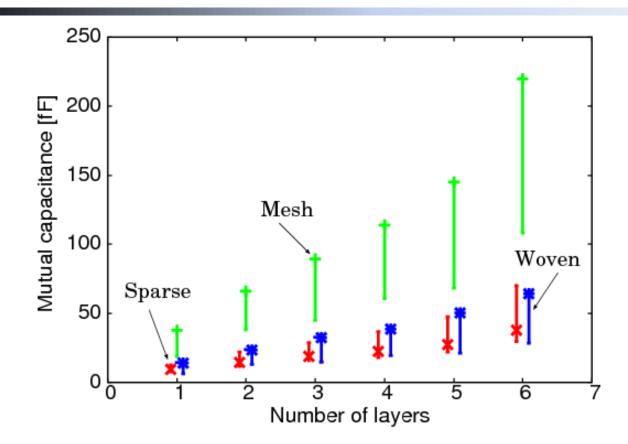


Note:

Coupling of Mesh is largest, but Inductor-Vdd coupling of Mesh is almost zero

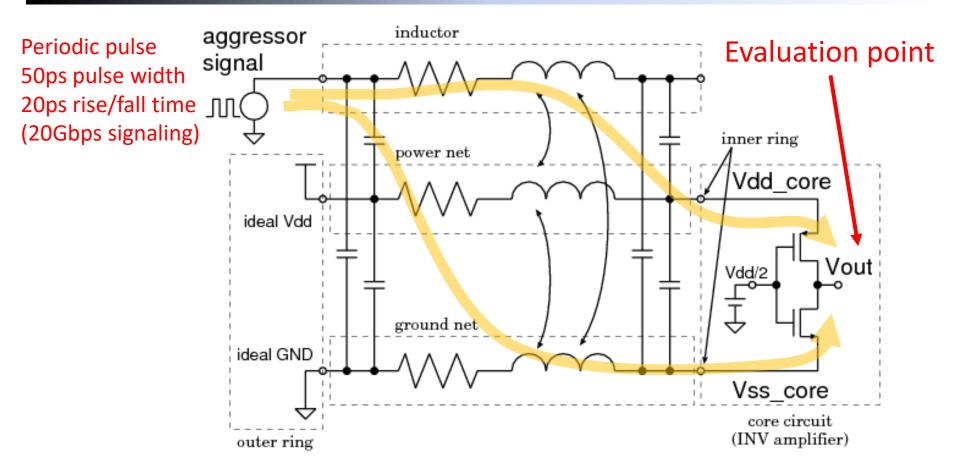
Sparse structure has larger coupling

Capacitive Coupling (Coupling Capacitance)



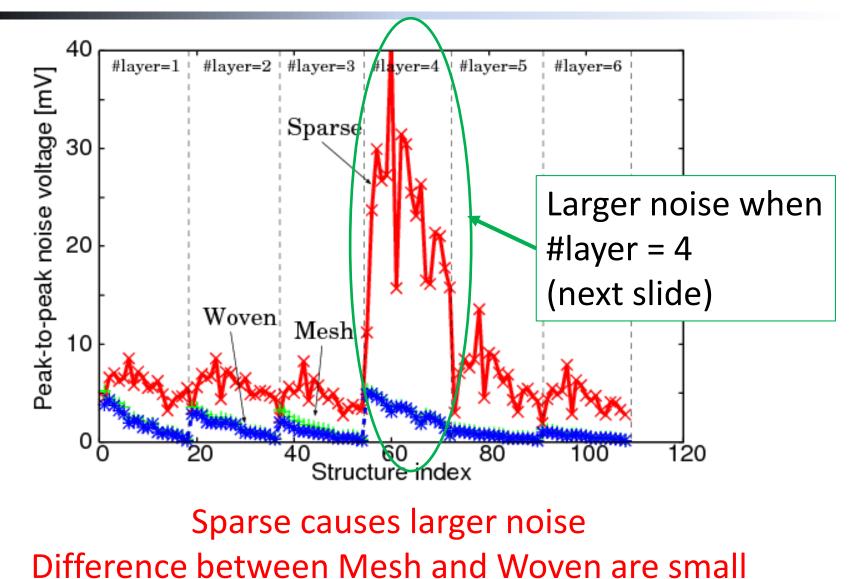
Sparse is small or comparable to Woven, but Woven has larger Vdd-GND capacitance -> Coupling coefficient of Sparse becomes larger

Transient Analysis on SPICE



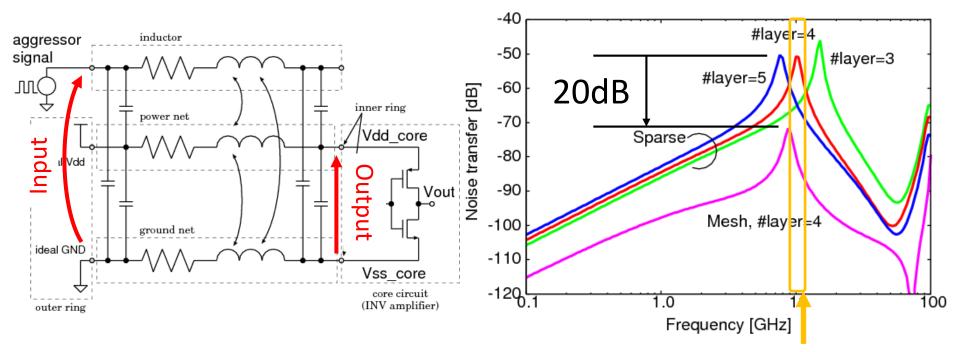
Coupled π -model for power/ground/inductor network

Noise Peak-to-peak Voltage



Impact of Resonance

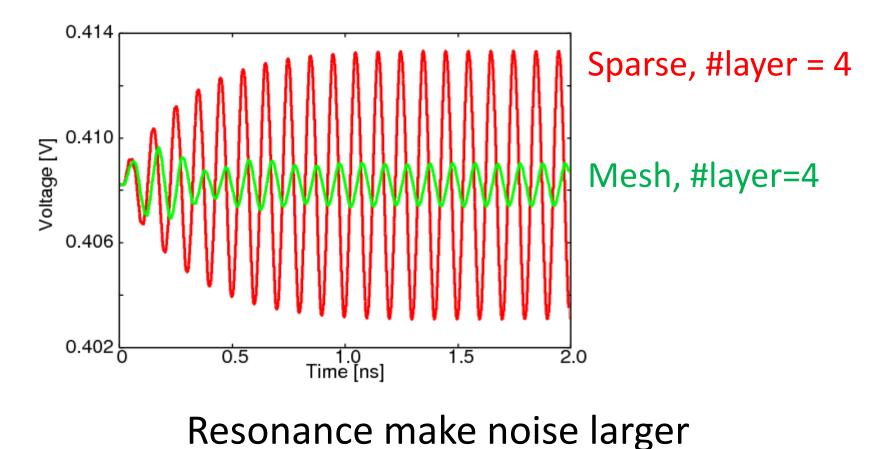
Noise transfer function from aggressor to inner ring



Aggressor input is 20Gbps = 10GHz clock

Mesh also has resonant frequency near 10 GHz, but transfer function is 20dB smaller

Noise Waveform



Mesh and Woven can reduce impact of resonance

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Summary

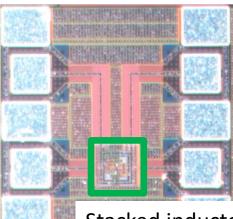
Coupling of inductor and PDN is investigated

- Stacking Inductor on circuit
- Test 3 structures: Sparse, Mesh, Woven
- PDN should have dense P/G wires
 - Even inductor get closer, Mesh and Woven are better than Sparse
 - Sparse has a risk of large noise due to resonance
 - Dense structure (Mesh and Woven) can suppress the impact of resonance

Future Work

Remaining questions:

- Coupling to substrate is not discussed
 - Mesh/Woven might shield coupling to substrate
- Is lumped model adequate?



Chip fabrication is completed Now we are preparing real chip measurement

Stacked inductor/amp.